

Title (en)

METHOD FOR DECONTAMINATING MICROLITHOGRAPHY PROJECTION LIGHTING DEVICES

Title (de)

VERFAHREN ZUR DEKONTAMINATION VON MIKROLITHOGRAPHIE-PROJEKTIONSBELICHTUNGSANLAGEN

Title (fr)

TECHNIQUE PERMETTANT DE DECONTAMINER LES DISPOSITIFS D'ECLAIRAGE PAR PROJECTION UTILISES EN MICROLITHOGRAPHIE

Publication

EP 1095315 A1 20010502 (DE)

Application

EP 99929261 A 19990617

Priority

- DE 19830438 A 19980708
- EP 9904210 W 19990617

Abstract (en)

[origin: DE19830438A1] The invention relates to a method for decontaminating microlithography projection lighting devices with optical elements (2) or parts thereof, especially the surfaces of optical elements, wherein a UV-light and a fluid are used. A second UV-light source (5) is directed towards at least one part of the optical element (2) during exposure pauses for decontamination.

IPC 1-7

G03F 7/20; **B08B 7/00**

IPC 8 full level

B08B 7/00 (2006.01); **G03F 7/20** (2006.01); **H01L 21/027** (2006.01)

CPC (source: EP KR US)

B08B 7/0057 (2013.01 - EP US); **G03F 7/7005** (2013.01 - EP US); **G03F 7/70058** (2013.01 - KR); **G03F 7/70116** (2013.01 - KR); **G03F 7/70141** (2013.01 - KR); **G03F 7/702** (2013.01 - KR); **G03F 7/70883** (2013.01 - EP US); **G03F 7/70925** (2013.01 - EP KR US); **G03F 7/70958** (2013.01 - KR)

Citation (search report)

See references of WO 0003304A1

Designated contracting state (EPC)

DE FR GB IE IT NL

DOCDB simple family (publication)

DE 19830438 A1 20000113; EP 1095315 A1 20010502; JP 2002520839 A 20020709; KR 100659698 B1 20061221; KR 20010053391 A 20010625; TW 425494 B 20010311; US 2001026402 A1 20011004; US 6936825 B2 20050830; WO 0003304 A1 20000120

DOCDB simple family (application)

DE 19830438 A 19980708; EP 9904210 W 19990617; EP 99929261 A 19990617; JP 2000559483 A 19990617; KR 20017000119 A 20010105; TW 88111039 A 19990630; US 75484101 A 20010103